

ABSTRACT

5 A substrate (101) subjected to a plasma process  
is placed on a first electrode (102). A magnetic field is  
applied to a surface of the substrate to which the plasma  
process is applied by magnetic field applying means (103).  
An auxiliary electrode (104) is provided on an outer  
periphery of the first electrode (102) to excite plasma on  
a back surface (105) thereof. Electrons in the plasma are  
10 caused to drift from a front surface (106) to a back  
surface (105) of the auxiliary electrode (104) and from  
the back surface (105) to the front surface (106) of the  
auxiliary electrode (104).

09827307-100404